

ABSTRACT

A halftone phase shift mask blank has a phase shifter
5 film on a transparent substrate. The phase shifter film is
composed of a metal silicide compound containing Mo, at least
one metal selected from Ta, Zr, Cr and W, and at least one
element selected from O, N and C. The halftone phase shift
mask blank has improved processability and high resistance to
10 chemicals, especially to alkaline chemicals.